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Optical properties of CuFeO₂ and CuFe_{1-x}Ga_xO₂ highly epitaxial thin films¹ A. L. CABRERA, R. A. WHEATLEY, S. ROJAS², Instituto de Fisica, Pontificia Universidad Catolica de Chile, T. JOSHI, P. BORISOV³, D. LEDERMAN, Department of Physics and Astronomy, West Virginia University, Morgantown — Delafossite thin films of 20 and 200 nm CuFeO₂ and 52 nm CuFe_{1-x}Ga_xO₂ were grown by Pulsed Laser Deposition (PLD) on Al₂O₃ (0001) substrates. High epitaxial quality of the films was verified by the techniques of X-Ray Diffraction and Raman spectroscopy. Optical transmission and reflection spectroscopies were performed on the films under vacuum and in CO₂ controlled atmosphere, respectively. Tauc plots based on transmission data yielded direct optical band gap at 2.4 eV, 2.8eV and 3.1eV and indirect band gap at 0.9 eV and 1.3 eV for CuFe_{1-x}Ga_xO₂ (x=0.25) and the direct band gap at 1.9eV, 3.1eV and the indirect band gap at 1.1eV for the CuFeO₂ films.

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